CLAIMS

1. A polishing cloth comprising, as forming materials of the polishing cloth, an unwoven fabric and a resin that is impregnated in the unwoven fabric, wherein

an apparent density is in a range of 0.30 g/cm^3 to 0.50 g/cm^3, and

a standard deviation of an abundance ratio of the forming materials is 21.7% or less, wherein the abundance ratio is measured in such a manner that the polishing cloth is sliced every 100 μm in the thickness direction from the front surface to the back surface to obtain slice surfaces in parallel to the front surface, followed by capturing images of two measurement surfaces each having a size of 2,000 μm × 2,000 μm (the two surfaces are positioned at different locations), and extracting 168 small areas each having a size of 100 μm × 100 μm in each of the measurement surfaces, the measurement of the abundance ratio being made to each of the small areas.

2. The polishing cloth according to claim 1, having a compression ratio of 5% or less.

3. The polishing cloth according to claim 1 or 2, wherein

a mean value of the abundance ratio of the forming materials is in a range of 22% to 45%.